Form PTO-1449

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INFORMATION DISCLOSURE CITATION IN AN APPLICATION

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Application Number

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Applicant Deboy et al.

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	4,593,302		06/03/86	Lidow et al	357	23.4	08/18/80				
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			01/23/90	Meyers et al.	431	41	05/17/88				
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Form PPO 44 P E

INFORMATION DISCLOSURE CITATION IN AN APPLICATION

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Docket Number (Optional)

Application Number

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Applicant Deboy et al.

Filing Date 04/22/99

Group Art Unit

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EP 0 939 44	16 A1	01/09/99	ЕРО	HOIL	29/08		x
WO 00/148	07	16.03.00	PCT	HOIL	29/78		χ
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U.S. DEPARTMENT OF COMMERCE

Form PTO 1749 E

INFORMATION DISCLOSURE CITATION IN AN APPLICATION (Use several sheets if necessary)

Docket Number (Optional)

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						CLASS	YES	NO	
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	IEEE	1981	J.P. Steng (p 422-42	gl, H. Strack, J. Tihanyi: "Power MOS Trans					
	ŒŒ	1981		c: "Effects of Drift Region Parameters n the	same prop	erties of P	ower LDM	OST"	
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